

Ion channeling for strain analysis in buried nanofilms (

Citation for published version (APA):

Selen, L. J. M., Janssen, F. J. J., IJzendoorn, van, L. J., Voigt, de, M. J. A., Theunissen, M. J. J., Smulders, P. J. M., & Eijkemans, T. J. (2002). Ion channeling for strain analysis in buried nanofilms (. *Journal of Applied Physics*, 91(8), 5507-5507.

Document status and date:

Published: 01/01/2002

Document Version:

Publisher's PDF, also known as Version of Record (includes final page, issue and volume numbers)

Please check the document version of this publication:

- A submitted manuscript is the version of the article upon submission and before peer-review. There can be important differences between the submitted version and the official published version of record. People interested in the research are advised to contact the author for the final version of the publication, or visit the DOI to the publisher's website.
- The final author version and the galley proof are versions of the publication after peer review.
- The final published version features the final layout of the paper including the volume, issue and page numbers.

[Link to publication](#)

General rights

Copyright and moral rights for the publications made accessible in the public portal are retained by the authors and/or other copyright owners and it is a condition of accessing publications that users recognise and abide by the legal requirements associated with these rights.

- Users may download and print one copy of any publication from the public portal for the purpose of private study or research.
- You may not further distribute the material or use it for any profit-making activity or commercial gain
- You may freely distribute the URL identifying the publication in the public portal.

If the publication is distributed under the terms of Article 25fa of the Dutch Copyright Act, indicated by the "Taverne" license above, please follow below link for the End User Agreement:

www.tue.nl/taverne

Take down policy

If you believe that this document breaches copyright please contact us at:

openaccess@tue.nl

providing details and we will investigate your claim.

Erratum: "Ion-channeling analysis of boron clusters in silicon" [J. Appl. Phys. 90, 4741 (2001)]

L. J. M. Selen, F. J. J. Janssen, L. J. van IJzendoorn,^{a)} and M. J. A. de Voigt
Research Institutes CPS and COBRA, Cyclotron Laboratory, Department of Applied Physics, Eindhoven University of Technology, P.O. Box 513, 5600 MB Eindhoven, The Netherlands

M. J. J. Theunissen
Phillips Research Laboratories, Eindhoven, The Netherlands

P. J. M. Smulders
Materials Science Center, University of Groningen, Groningen, The Netherlands

T. J. Eijkemans
Research School Cobra, Department of Applied Physics, Eindhoven University of Technology, Eindhoven, The Netherlands

[DOI: 10.1063/1.1463446]

The title of the paper should have been: "Ion channeling for strain analysis in buried nanofilms (<6 nm)." In addition, three references appeared incorrectly; corrected versions of Refs. 1, 7, and 13 follow:

¹B. D. Cullity, *Elements of X-Ray Diffraction* (Addison-Wesley, Reading, MA, 1976).

⁷T. C. Q. Noakes, P. Baily, P. K. Hucknall, K. Donovan, and M. A. Howson, *Phys. Rev. B* **58**, 4934 (1998).

¹³J. Lindhard and K. Dan., *Vidensk. Selsk. Mat. Fys. Medd.* **1965**, 34.

^{a)}Author to whom correspondence should be addressed. Present address: Cyclotron Laboratory, Department of Applied Physics, Eindhoven University of Technology, P.O. Box 513, 5600 MB Eindhoven, The Netherlands; electronic mail: L.J.van.IJzendoorn@tue.nl.